

IN THE CLAIMS:

Please amend Claims 8, 15, and 28 as follows.

1 - 7. (Cancelled)

8. (Currently Amended) A method of producing a corrosion-resistant article for use in semiconductor processing apparatus, comprising:

providing an article including a body formed from a high purity aluminum alloy, wherein said alloy includes mobile impurities present at the following concentrations, magnesium at up to 4.0 weight %, silicon at up to 0.03 weight %, iron at up to 0.03 weight %, copper at up to 0.07 weight %, manganese at up to 0.015 weight %, zinc at up to 0.16 weight %, chromium at up to 0.07 weight %, titanium at up to 0.01 weight %, and wherein a total of other impurities present in said aluminum alloy ranges from 0 - 0.1 weight %, with individual other impurities limited to 0 - 0.03 weight % each, and wherein said alloy mobile impurity particulates are controlled within limits so that at least 95 % of all particles are 5  $\mu$ m or less in size, no more than 5 % of said particles range between 20  $\mu$ m and 5 $\mu$ m, and no more than 0.2 % of said particles range between 50  $\mu$ m and 20  $\mu$ m;

chemically cleaning at least one surface of said article body by contacting said surface with an acidic solution including phosphoric acid and nitric acid;

rinsing said at least one chemically cleaned surface to remove residual acidic solution;  
and

forming over said at least one surface of said high purity aluminum alloy body an aluminum-oxide comprising film, whereby said at least one surface ~~becomes corrosion-resistant~~  
~~to~~ is protected from corrosion by a corrosive environment.

9. (Original) A method in accordance with Claim 8, wherein no more than 0.1 % of said particles range between 50  $\mu\text{m}$  and 20  $\mu\text{m}$ .
10. (Original) A method in accordance with Claim 9, wherein no more than 0.1 % of said particles range between 40  $\mu\text{m}$  and 20  $\mu\text{m}$ .
11. (Original) A method in accordance with Claim 10, wherein no more than 0.2 % of said particles range between 40  $\mu\text{m}$  and 20  $\mu\text{m}$ .
12. (Original) A method in accordance with Claim 8, wherein said particulates are formed from mobile impurities selected from the group consisting of magnesium, silicon, iron, copper, manganese, zinc, chromium, titanium, and compounds thereof.
13. (Cancelled)
14. (Original) A method in accordance with Claim 13, wherein said magnesium is present at a concentration ranging between about 3.5 weight % and about 4.0 weight %.
15. (Currently Amended) A method in accordance with Claim 8 or Claim 10, or Claim ~~13~~ 11 or Claim 14, wherein said corrosion-resistance is with respect to active halogen-containing species.
16. (Original) A method in accordance with Claim 15, wherein said active halogen-containing species are present in the form of a plasma.

17. (Previously Presented) A method of creating an aluminum oxide protective film on the surface of a high purity aluminum alloy, comprising:

providing an aluminum alloy, wherein said alloy includes mobile impurities present at the following concentrations, magnesium at up to 4.0 weight %, silicon at up to 0.03 weight %, iron at up to 0.03 weight %, copper at up to 0.07 weight %, manganese at up to 0.015 weight %, zinc at up to 0.16 weight %, chromium at up to 0.07 weight %, titanium at up to 0.01 weight %, and wherein a total of other impurities present in said aluminum alloy ranges from 0 - 0.1 weight %, with individual other impurities limited to 0 - 0.03 weight % each, and wherein said alloy mobile impurity particulates are limited so that at least 95 % of all particles have a particle size of less than 5  $\mu\text{m}$ , no more than 5 % of said particles have a particle size ranging between 20  $\mu\text{m}$  and 5  $\mu\text{m}$ , and no more than 0.2 % of said particles have a particle size ranging between 50  $\mu\text{m}$  and 20  $\mu\text{m}$ ; and

exposing said surface of said aluminum alloy to an electrolytic oxidation process during which said surface is immersed as an anode in an acid electrolyte, with a cathode comprised of an aluminum alloy, and wherein a DC current is applied, wherein said acid electrolyte is a water-based solution comprising 10 % to 20 % by weight sulfuric acid and about 0.5 % to 3.0 % by weight oxalic acid, wherein said protective film is created at a temperature ranging from about 5°C to about 25°C, and wherein an applied current density of said DC current ranges from 5 A/ft<sup>2</sup> to 36 A/ft<sup>2</sup>, whereby an improved transition from the aluminum alloy surface to the aluminum oxide layer is provided, which improves the performance of the article.

18. (Original) A method according to Claim 17, wherein, prior to exposing said aluminum alloy surface to said electrolytic oxidation process, said surface is cleaned by contacting said surface with an acidic solution which includes about 60 % to 90 % by weight of technical grade phosphoric acid, having a specific gravity of about 1.7, and about 1% - 3 % by weight of nitric acid, wherein said cleaning is carried out with said aluminum alloy surface at a temperature in

the range of about 100°C, for a time period ranging from about 30 seconds to about 120 seconds.

19. (Original) A method in accordance with Claim 18, wherein subsequent to said cleaning of said aluminum alloy surface and prior to said electrolytic oxidation process, said surface is rinsed with a deionized water rinse.

20. (Original) A method in accordance with Claim 17, or Claim 18, or Claim 19, wherein said aluminum oxide protective film exhibits hexagonal cells having internal pores ranging in size from about 300 Å to about 750 Å in diameter.

21 - 23. (Cancelled)

24. (Original) A method in accordance with Claim 17, wherein, prior to creating said aluminum oxide protective film on said high purity aluminum alloy surface, said aluminum alloy is heat treated to relieve stress and increase hardness, wherein said heat treatment is carried out at a temperature of 330°C or at a lower temperature.

25. (Original) A method in accordance with Claim 18 or Claim 19, wherein, prior to creating said aluminum oxide protective film on said high purity aluminum alloy surface, said aluminum alloy is heat treated to relieve stress and increase hardness, wherein said heat treatment is carried out at a temperature of 330°C or at a lower temperature.

26 - 27. (Cancelled)

28. (Currently Amended) A method of creating an aluminum oxide protective film on the surface of a high purity aluminum alloy, comprising:

providing an aluminum alloy, wherein said alloy includes mobile impurities present at the following concentrations ~~or at lower concentrations~~, magnesium at a concentration ranging from about 3.5 weight % to 4.0 weight %, silicon at a concentration ranging from 0 weight % to 0.03 weight %, iron at a concentration ranging from 0 weight % to 0.03 weight %, copper at a concentration ranging from about 0.02 weight % to 0.07 weight %, manganese at a concentration ranging from about 0.005 weight % to 0.015 weight %, zinc at a concentration ranging from about 0.08 % to 0.16 weight %, chromium at a concentration ranging from about 0.02 % to 0.07 weight %, titanium at a concentration ranging from 0 weight % to 0.01 weight %, and wherein a total of other impurities present in said aluminum alloy ranges from 0 - 0.1 weight %, with individual other impurities limited to 0 - 0.03 weight % each; and

exposing said surface of said aluminum alloy to an electrolytic oxidation process during which said surface is immersed as an anode in an acid electrolyte, with a cathode comprised of an aluminum alloy, and wherein a DC current is applied, wherein said acid electrolyte is a water-based solution comprising 10 % to 20 % by weight sulfuric acid and about 0.5 % to 3.0 % by weight oxalic acid, wherein said protective film is created at a temperature ranging from about 5 °C to about 25 °C, and wherein an applied current density of said DC current ranges from 5 A/ft<sup>2</sup> to 36 A/ft<sup>2</sup>.

29. (Previously Presented) A method according to Claim 28, wherein, prior to exposing said aluminum alloy surface to said electrolytic oxidation process, said surface is cleaned by contacting said surface with an acidic solution which includes about 60 % to 90 % by weight of technical grade phosphoric acid, having a specific gravity of about 1.7, and about 1% - 3 % by weight of nitric acid, wherein said cleaning is carried out with said aluminum alloy surface at a

temperature in the range of about 100°C, for a time period ranging from about 30 seconds to about 120 seconds.

30. (Previously Presented) A method in accordance with Claim 29, wherein subsequent to said cleaning of said aluminum alloy surface and prior to said electrolytic oxidation process, said surface is rinsed with a deionized water rinse.

31. (Previously Presented) A method in accordance with Claim 28, or Claim 29, or Claim 30, wherein said aluminum oxide protective film exhibits hexagonal cells having internal pores ranging in size from about 300 Å to about 750 Å in diameter.

32. (Previously Presented) A method in accordance with Claim 28, or Claim 29, or Claim 30, wherein mobile impurity particulates present in said high purity aluminum alloy are limited so that at least 95 % of all particles have a particle size of less than 5 µm, no more than 5 % of said particles have a particle size ranging between 20 µm and 5 µm, and no more than 0.2 % of said particles have a particle size ranging between 50 µm and 20 µm.

33. (Previously Presented) A method in accordance with Claim 28, or Claim 29, or Claim 30, wherein, prior to creating said aluminum oxide protective film on said high purity aluminum alloy surface, said aluminum alloy is heat treated to relieve stress and increase hardness, wherein said heat treatment is carried out at a temperature of 330°C or at a lower temperature.

34. (Previously Presented) A method in accordance with Claim 32, wherein, prior to creating said aluminum oxide protective film on said high purity aluminum alloy surface, said aluminum alloy is heat treated to relieve stress and increase hardness, wherein said heat treatment is carried out at a temperature of 330°C or at a lower temperature.